

FIRST INFORMATION DISCLOSURE STATEMENT BY APPLICANT

(use as many sheets as necessary)

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Complete if Known

Application Number: 10/709,622
 Filing Date: May 18, 2004
 First Named Inventor: Hiroshi Nogami
 Examiner Name: JEFFRIE ROBERT LUND
 Attorney Docket Number: 001425-126

U.S. PATENT DOCUMENTS

Examiner Initials	Document Number	Kind Code (if known)	Name of Patentee or Applicant of Cited Document	Issue/Publication Date (MM-DD-YYYY)
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ALW	4,792,378		Rose et al.	12-20-1998
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					Translation	Partial Translation	Eng. Lang. Summary	Search Report	IPER	Abstract Cited in Spec
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ALW	2837087		Japan	10-09-1998						
ALW	6-260434		Japan	09-16-1994						X
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Examiner Signature: *[Signature]* Date Considered: 5/2/05

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with M.P.E.P. § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

Substitute for form 1449A/PTO & 1449B/PTO		Complete if Known	
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		Filing Date	May 18, 2004
		First Named Inventor	Hiroshi Nogami
		Examiner Name	JEFFRIE ROBERT LUND
		Attorney Docket Number	001425-126
Sheet	1 of 2		

NON-PATENT LITERATURE DOCUMENTS	
Examiner Initials	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.
AK	Shingo KADOMURA et al., "ANISOTROPIC ETCHING USING DEPOSITION OF SULFUR, Sony Corporation, Semiconductor World, January 1993, pp. 1-11, and translation
AK	Ken FUJITA et al., "X-RAY PHOTOELECTRON SPECTROSCOPIC STUDIES ON PYROLYSIS OF PLASMA-POLYMERIZED FLUOROCARBON FILMS ON Si", Jpn. J. Appl. Phys. volume 34 (1995), pp. 304-306, Part 1, NO. 1, January 1995
AK	Robert C. REID et al., "THE PROPERTIES OF GASES AND LIQUIDS", McGraw-Hill, Inc., Appendix B, Index
AK	R. Byron BIRD et al., "TRANSPORT PHENOMENA", Jon Wiley & Sons, pp. 508-509 and 512-513
AK	Riccardo d'AGOSTINO et al., "PLASMA ETCHING OF Si and SiO ₂ in SF ₆ -O ₂ MIXTURES", J. Appl. Phys. 52(1), January 1981, pp. 162-167
AK	Robert C. REID et al. "Lennard-Jones Potentials as Determined from Viscosity Data (Appendix B)", <i>The Properties of Gases and Liquids</i> , McGraw-Hill, Inc., Copyright 1987, p.734, Index
AK	R. Byron BIRD et al. "Diffusivity and the Mechanisms of Mass Transport; Theory of Ordinary Diffusion in Gases at Low Density", <i>Transport Phenomena</i> , John Wiley & Sons, Inc., Copyright 1960, p. 508-513
AK	A new technique for diagnostics of a radio-frequency parallel-plate remote plasma; N. Sano et al.; Appl. Phys. Lett 65 (2), 11 July 1994 pages 162-164.
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AK	Improvement of structural and electrical properties in low-temperature gate oxides for poly-Si TFTs by controlling O ₂ /SiH ₄ ratios; AM-LCD 1997; pages 87-90.
AK	"Flow of Atoms and Molecules—Rarefied Gas Dynamics and its Applications", section 2.6.4, The Japan Society of Mechanical Engineers, 1996, Kyoritsu Shuppan Co., Ltd.

Examiner Signature	<i>[Signature]</i>	Date Considered	5/2/05
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*EXAMINER: Initial reference considered, whether or not citation is in conformance with M.P.E.P. § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.